Electronic Supplementary Information

Synergistic effect of Ga doping and Mg alloying over the enhancement of Ga doped MgZnO pressure sensor

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Table s1: Composition data of elements in Ga doped MgZnO thin films

Sample	Ga (at. %)	Mg (at. %)	Zn (at. %)	X _{Mg} = Mg(at %) / Zn+M g+Ga (at. %)	X _{Ga} = Ga(at%) / Zn+Mg+Ga (at. %)
Mg _{0.28} Zn _{0.72} O	-	11.59	29.05	0.285	0
MZO,G30	0.56	12.12	28.95	0.291	0.014
MZO,G40	1.18	12.86	28.43	0.302	0.027
MZO,G50	1.77	12.69	28.21	0.297	0.041
MZO,G60	2.66	11.47	28.31	0.270	0.062
MZO,G70	2.96	11.9	29.53	0.268	0.066
MZO,G80	3.19	10.86	28.04	0.258	0.076



Fig. s1: XRD spectra of Ga doped MgZnO films ($2\theta = 20^{\circ}-80^{\circ}$)

Band gap in Ga doped MgZnO thin films

The band gap (E_g) in Ga doped MgZnO thin film is estimated by using following equations: $\alpha h v = c(hv-Eg)^{1/2}$, $\alpha =$ absorption coefficient, h = planck's constant, v(frequency) = c/λ , c= speed of light, E_g = band gap. The absorption coefficient (α) and the percentage of transmittance (%T) in Figure 5(a) are related by the equation: $\alpha =$ (2.3026/t)×log₁₀(100/%T), t = thickness of the CZNA. The band gap is estimated by the extrapolation of the linear portion of the plot between (αhv)² with hv as shown below.





Fig. s2: Bang gap of MgZnO with different Ga doping concentrations

Piezoelectric coefficient in Ga doped MgZnO thin films

Piezoelectric constants were obtained by piezo-response force microscopy (PFM) of a multi-functional scanning probe microscope (Bruker Dimension ICON). The PFM technique is based on the detection of local vibrations of a sample induced by an AC signal applied between the conductive tip of AFM and the bottom electrode of the sample [Ref. s1, Ref. s2]. The local oscillations of the sample surface are transmitted to the tip and detected by using a lock-in amplifier. The resulting movement of the tip is detected by the photodiode and so the minute surface displacement is converted into an oscillating voltage. In our experiments, the voltage is applied in steps (1V, 3V, 5V) through computer control, and the output voltage corresponding to the minute displacement at the AFM tip was recorded using a lock-in amplifier. The piezoelectric constant can be determined from the slope of the minute displacement vs applied voltage plot by the following equation.

Piezoelectric constant $(d_{33}) = (slope of the GaMgZnO/slope of ZnO) \times 12.4 (standard).$

Fig. s4 shows the output voltage vs. applied voltage plot along with the slope and the corresponding piezoelectric coefficient for few Ga doped MgZnO samples. Table s2 summarizes the detail PFM analysis data and the piezoelectric coefficient for all the Ga doped MgZnO samples.



Fig. s3: Piezoelectric coefficient (d₃₃) from PFM data

Table s2: PFM data analysis for piezoelectric coefficient (d₃₃)

R.f power of	X _{Ga}	Slope	Piezoelectric
Ga ₂ O ₃ target			coefficient
			(d ₃₃)
0	0	1.875×10-4	23.25
30	0.01345	1.45×10-4	17.98
40	0.02778	2.675×10-4	33.17
50	0.04148	2.35×10-4	29.14
60	0.06268	1.075×10 ⁻⁴	13.33
70	0.06668	3×10-5	3.72
80	0.07579	2.25×10 ⁻⁵	2.79

Ref. s1: M.-H. Zhao, Z.-L. Wang, S. X. Mao, Piezoelectric Characterization of Individual Zinc Oxide Nanobelt Probed by Piezoresponse Force Microscope, Nano letter, 4(4), (2004) 587-590

Ref s2: J. A. Christman, R. R. Woolcott, Jr., A. I. Kingon, R. J. Nemanicha, Piezoelectric measurements with atomic force microscopy, Appl. Phys. Lett. 73, 26, (1998) 3851-3853



Fig. s4: Variation of c axis lattice parameter with Ga doping concentration.

Weigh	Force	Stress	Stress	Force and stress calculation
t	(N)	(Pa)	(MPa)	(Film area = 3 cm^2)
(kg)				
0	0	0	0	For 0.2 kg,
0.2	1.96	6533	0.00653	Force = $0.2 \ kg \times 9.8 \frac{m}{r^2} = 1.96 \ N$
0.5	4.9	16333	0.01633	s^2
				$Stress = \frac{1.96 N}{3 \times 10^{-4} m^2} = 6533.33 \frac{N}{m^2} = 6533.33 pc$

Table s4: Stress sensitivity of Ga:MgZnO thin film with Ga doping concentration

Ga doping	Unstressed	Stressed	Sensitivity of	Stress
concentration	current (A) at	current (A) at	change in current	sensitivity
	5V	5V,	$\frac{\Delta I}{I} = \frac{I(\epsilon) - I(0)}{I(0)}$	(MPa ⁻¹)
		(0.2 kgf,	$\overline{I} = \overline{I(0)}$	$\Delta I/I$
		0.00653 MPa)		stress
0	6.98461×10 ⁻⁴	8.28462×10 ⁻⁴	0.18613	28.50
0.027	8.57008×10 ⁻⁴	0.00103	0.20482	31.36
0.041	0.00252	0.00294	0.16692	25.56

Different	Current	SBH (meV)	Sensitivity of	Stress
loadings	(A) at	at different	change in current	sensitivity
	different	load	$\Delta I \ I(\varepsilon) - I(0)$	(MPa ⁻¹)
	load		$\frac{1}{I} = \frac{1}{I(0)}$	$\Delta I/I$
				stress
0	0.00243	0	0	0
0.2	0.00294	-4.9	0.21	32.14
0.5	0.00361	-10.5	0.48	29.75

Table s5: Stress sensitivity of Ga:MgZnO thin film with load

Limit of detection and detection range

We have taken a series of I~V curves at zero load to find out the minimum detection limit and the stability of the device output.

No. of Run		Current (A)	Variation of sensitivity at zero load	% change
Kull	(V)	Current (A)	10au	
1	5	4.43E-04	0.00E+00	0.0%
2	5	4.53E-04	-2.25E-02	-2.2%
3	5	4.40E-04	7.79E-03	0.8%
4	5	4.43E-04	1.24E-03	0.1%
5	5	4.41E-04	5.26E-03	0.5%
6	5	4.43E-04	-4.61E-04	0.0%
7	5	4.43E-04	1.66E-04	0.0%
8	5	4.47E-04	-7.39E-03	-0.7%
9	5	4.38E-04	1.11E-02	1.1%
10	5	4.42E-04	2.50E-03	0.2%



Figure s5: Detection limit and detection range

- Here, we can see the error bar created at zero load for a series of I~V measurements.
- The maximum change in current (sensitivity) we can obtain is around 0.01.
- We know the sensitivity value of 0.21 corresponding to a compressive stress of 6533 Pa.
- The corresponding pressure for 0.01 is [6533*0.01/0.21] = 311.0952 Pa.
- Thus, this calculation defines the pressure less than 312 Pa will not be detected.

Stablility test

- The stability/ repeatability study has been done by taking i-t curve (Current vs time) at a constant bias of 5V.
- The repeated load is provided by applying force against the sample several time.



Figure s6: Stability of Ga:MgZnO pressure sensor